



Sheet 1 of 1

Form 1449\*

Atty. Docket No.: 303.278US1

Serial No. 08/902,809

INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT

(Use several sheets if necessary)

Applicant: Klaus Florian Schuegraf et al.

Filing Date: July 30, 1997

Group: 2503

## U.S. PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
ON	5,087,584	02/11/1992	Wada, et al.	437	43	04/30/90
ON	5,103,272	04/07/1992	Nishiyama	357	23.4	03/20/90
ON	5,268,330	12/07/1993	Givens, et al.	437	195	12/11/92
ON	5,382,551	01/17/1995	Thakur, et al.	437	247	04/09/93
ON	5,422,291	06/06/1995	Clementi, et al.	437	43	05/26/93
ON	5,425,392	06/20/1995	Thakur, et al.	437	173	05/26/93
ON	5,438,016	08/01/1995	Figura, et al.	437	67	03/02/94
ON	5,439,838	08/08/1995	Yang	437	43	09/14/94
ON	5,545,578	08/13/1996	Park, et al.	437	44	05/15/95
ON	5,597,756	01/28/1997	Fazan, et al.	437	52	06/21/95
ON	5,624,865	04/29/1997	Schuegraf, et al.	438	396	10/13/95
ON	5,668,394	09/16/1997	Lur, et al.	257	413	01/03/96

## FOREIGN PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes   No
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## OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

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ON	Beyers, R., "Thermodynamic Considerations in Refractory Metal Silicon-Oxygen Systems", <u>J. Appl. Phys.</u> , 56, 147-152, (July 1984)
ON	Kasai, K., et al., "W/WNx/Poly-Si Gate Technology for Future High Speed Deep Submicron CMOS LSIs", <u>International Electron Devices Meeting</u> , 497-500, (1994)
ON	Lee, D.H., et al., "Gate Oxide Integrity (GOI) of MOS transistors with W/TiN stacked gate", <u>1996 Symposium on VLSI Technology Digest of Technical Papers</u> , 208-209, (1996)

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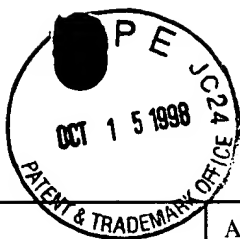
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Applicant: Klaus Florian Schuegraf et al.

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**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
ON	5,538,906	07/23/1996	Aoki, H.	437	29	01/30/95
ON	5,681,768	10/28/1997	Smayling, M.C., et al.	437	41	06/07/95
ON	5,739,066	04/14/1998	Pan, P.	438	595	09/17/96

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**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes   No
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## OTHER DOCUMENTS

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